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Patent
Attorney's Docket No. 015290-517

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of)	
Tuqiang NI et al.)	Group Art Unit: Not Yet Assigned
Application No.: Not Yet Assigned)	Examiner: Not Yet Assigned
Filed: February 21, 2001)	
For: GAS INJECTION SYSTEM FOR PLASMA PROCESSING)	

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Prior to examination, please amend the above-identified application as follows:

IN THE CLAIMS:

Please cancel Claim 1 and add new Claims 25-36 as follows:

25. A gas injector for supplying process gas to a plasma processing chamber wherein a semiconductor substrate is subjected to plasma processing, the gas injector comprising:
gas injector body sized to extend through a chamber wall of the processing chamber such that a distal end of the gas injector body is exposed within the processing chamber, the gas injector body including a plurality of gas outlets adapted to supply process gas into the processing chamber.

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